

ABSTRACT

To provide a mask for film-forming by which deposition films can be removed and cleaned without damage to a mask and the cleaning operation is improved. It is provided
5 with a mask body 2 arranged on a substrate W, having an opening 20 for limiting a film-forming region on the substrate W; and

Cover 3 for covering a predetermined region on a surface of the mask body 2. The cover is an assembly of segments 3A, 3B and 3C mountably and demountably attached to the mask body. Deposition film can be prevented from adhering to the mask body by the
10 cover 3. The mask body is not damaged in the cleaning operation. Deposited films can be removed from the individual cover segments 3A, 3B and 3C. The cleaning operation is simplified. The mask can be easily large-sized.